

	Hit s	Search Text	DBs
19	27	((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive)) and (modulat\$4 or (spatial near14 modulat\$4) or SLM or deflect\$4 or acousto\$6) and ((immers\$4 near12 (liquid or fluid)) same (inlet or outlet or port or input or output))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
20	10	((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive)) and (modulat\$4 or (spatial near14 modulat\$4) or SLM or deflect\$4 or acousto\$6) and (immers\$4 near9 (liquid or fluid)) and ((capillary near9 force) or capillarit\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
21	44	((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive)) and (modulat\$4 or (spatial near14 modulat\$4) or SLM or deflect\$4 or acousto\$6) and ((immers\$4 near12 (liquid or fluid)) same (inlet or outlet or port or input or output or passag\$5))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB